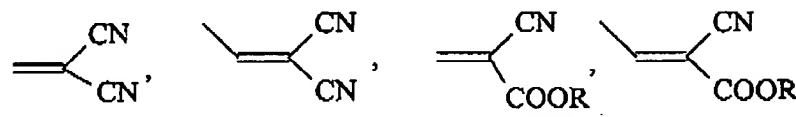


Serial No. 09/853.732  
Filing Date May 11, 2001

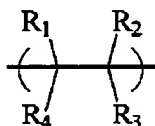
Customer No. 26,289

### Listing of the claims

1. (Currently Amended) A photoresist composition comprising a copolymer, a photoactive component, and a solvent, where the copolymer comprises at least one ethylenic unit of ~~structure 1 containing at least one cyano functionality,~~  
derived from monomers selected from



where R is (C<sub>1</sub>–C<sub>10</sub>)alkyl, and at least one cyclic unit of structure 2, where ~~structure 1 is selected from~~

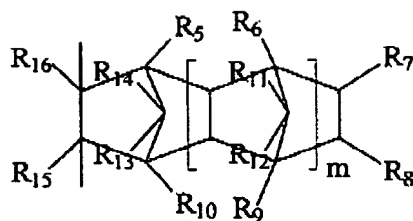


(1)

where, ~~R<sub>1</sub>, R<sub>4</sub> are independently hydrogen, alkyl, O-alkyl, alkyl ester, perfluoroalkyl ester, carboxylic acid, alkylcarbonyl, carboxylate, cyano(CN), fluoroalkyl, acid or base labile group, alkylsulfonyl, sulfonate, sulfonamide, alkylsulfonamide, providing that at least one of R<sub>1</sub>, R<sub>4</sub> contains a cyano functionality,~~ and where structure 2 is

Serial No. 09/853.732  
Filing Date May 11, 2001

Customer No. 26,289



(2)

where R<sub>5</sub>-R<sub>14</sub> are independently hydrogen, (C<sub>1</sub>-C<sub>8</sub>)alkyl, halogen, carboxylic acid, (C<sub>1</sub>-C<sub>10</sub>)alkylOCOalkyl, cyano(CN), (C<sub>1</sub>-C<sub>10</sub>) secondary or tertiary carboxylate, substituted pinacol, fluoroalkyl, an acid labile group, a base labile group, W(CF<sub>3</sub>)<sub>2</sub>OH is capped and wherein W is (C<sub>1</sub>-C<sub>8</sub>)alkyl or (C<sub>1</sub>-C<sub>6</sub>)alkyl ether, and wherein R<sub>7</sub> and R<sub>8</sub> may be linked to form a cyclic non-aromatic structure,

R<sub>15</sub> and R<sub>16</sub> are hydrogen or (C<sub>1</sub>-C<sub>4</sub>)alkyl,  
and m is 0-3.

2. (previously presented) The photoresist composition according to claim 1, where the acid labile group is selected from tert-butoxycarbonyl, tert-pentyloxycarbonyl, isobornyloxycarbonyl, cyclohexyloxycarbonyl, 2-alkyl-2-admantyloxycarbonyl, tetrahydrofuranyloxycarbonyl, tetrahydropyranyloxycarbonyl, substituted or unsubstituted methoxymethoxycarbonyl, β-carbonyloxy-β-methyl-δ-valerolactone, β-carbonyloxy-β-methyl-γ-butyrolactone, tert-butoxycarbonyloxy, tert-pentyloxycarbonyloxy, isobornyloxycarbonyloxy, cyclohexyloxycarbonyloxy, 2-alkyl-2-admantyloxycarbonyloxy, tetrahydrofuranyloxycarbonyloxy, tetrahydropyranyloxycarbonyloxy, substituted or unsubstituted methoxymethoxycarbonyloxy, β-oxy-carbonyloxy-β-methyl-δ-valerolactone, β-oxy-carbonyloxy-β-methyl-γ-butyrolactone, tert-butoxy, tert-pentyloxy, isobornyloxy, cyclohexyloxy, 2-alkyl-2-admantyloxy, tetrahydrofuranyloxy, tetrahydropyranyloxy, substituted or unsubstituted methoxymethoxy, β-oxy-β-

Serial No. 09/853.732  
Filing Date May 11, 2001

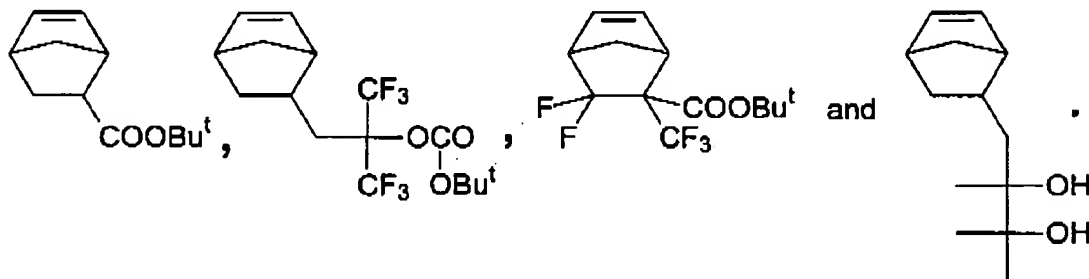
Customer No. 26,289

methyl- $\delta$ -valerolactone, and  $\beta$ -oxy- $\beta$ -methyl- $\gamma$ -butyrolactone, and where the acid labile group is connected directly to the polymer backbone or through a connecting group.

3. (previously presented): The photoresist composition according to claim 1, where the nonaromatic structure is a lactone or anhydride.

4. (canceled)

5. (previously presented): The photoresist composition according to claim 1, where the cyclic unit is derived from monomers selected from



6. (previously presented): The photoresist composition according to claim 1, where the ethylenic unit is at a level of at least 40 mole %.

7. (previously presented): The photoresist composition according to claim 1, where the ethylenic unit is at a level less than 80 mole %.

8. (previously presented): The photoresist composition according to claim 1, where the weight average molecular weight is less than 200,000.

9. (previously presented): The photoresist composition according to claim 1, where the weight average molecular weight is greater than 1,000.

Serial No. 09/853.732  
Filing Date May 11, 2001

Customer No. 26,289

10. (previously presented): The photoresist composition according to claim 1, further comprising additional comonomers.
11. (previously presented): The photoresist composition according to claim 10, where the additional comonomers are selected from acrylates, methacrylates, styrenes, hydroxystyrene, hydroxyhexafluoroisopropylstyrene, vinyl ethers, vinyl acetates, tetrafluoroethylene, maleic anhydride and itaconic anhydride and their fluorinated homologues.
12. (previously presented): The photoresist composition according to claim 10, where the additional monomer is at a level less than 30 mole%.
13. (previously presented): The photoresist composition according to claim 1, where the copolymer has an absorption coefficient at an exposure wavelength of less than 4/micron.
14. (previously presented): The photoresist composition according to claim 1, where the solvent is selected from propylene glycol mono-alkyl ether, propylene glycol alkyl ether acetate, butyl acetate, xylene, ethylene glycol monoethyl ether acetate, propylene glycol mono-methyl ether acetate, 2-heptanone, ethyl lactate, ethyl-3-ethoxypropionate, mixtures of ethyl lactate and ethyl-3-ethoxypropionate, and mixtures thereof.
15. (previously presented): The photoresist composition according to claim 1, further comprising a dissolution inhibitor.
16. (previously presented): The photoresist composition according to claim 1, where the photoactive component is selected from a photoacid generator, a photobase generator or mixtures thereof.

Serial No. 09/853.732  
Filing Date May 11, 2001

Customer No. 26,289

17. (previously presented): The photoresist composition according to claim 13, where the photoacid generator is selected from diazonium salts, iodonium salts, sulfonium salts, sulfones, hydroxamic acid esters, halides and sulfonic esters.

18. (previously presented): The photoresist composition according to claim 1, further comprising a base.

19. (previously presented): The photoresist composition according to claim 18, where the base is selected from triethylamine, triethanolamine, aniline, ethylenediamine, pyridine, triphenyliodonium hydroxide, dialkylodonium hydroxide, and trialkylsulfonium hydroxide.

20. (previously canceled)

21. (original)        The process of imaging a photoresist composition comprising the steps of:

- a)     coating a substrate with a film of photoresist composition of claim 1;
- b)     baking the substrate to substantially remove the solvent;
- c)     imagewise irradiating the photoresist film;
- d)     baking the photoresist film; and,
- e)     developing the irradiated photoresist film using an alkali developer.

22. (original). The process of claim 21, wherein the photoresist film is imagewise irradiated using light of wavelength in the range of 100nm to 300nm.

23. (original). The process of claim 21, wherein the heating in step d) ranges from a temperature of from about 90°C to about 150°C for from about 30 seconds to about 180 seconds on a hot plate or from about 15 minutes to about 40 minutes in an oven.

Serial No. 09/853.732  
Filing Date May 11, 2001

Customer No. 26,289

24. (original). The process of claim 21, wherein the alkali developer comprises an aqueous solution of tetramethyl ammonium hydroxide.

25. (canceled)